METHODS, COMPLEXES, AND SYSTEMS FOR FORMING METAL-CONTAINING FILMS ON SEMICONDUCTOR STRUCTURES

Abstract of the Disclosure

A method of forming a film on a substrate using Group IVB, VB, or VIB metal complexes. The methods are particularly suitable for the preparation of semiconductor structures using chemical vapor deposition techniques and systems.

*EXPRESS MAIL" MAILING LABEL NUMBER <u>EL 776963676</u>US

DATE OF DEPOSIT 25 May 2001

I HEREBY CERTIFY THAT THIS PAPER OR FEB IS BEING DEPOSITED WITH THE UNITED STATES POSTAL SRVICE "EXPRESS MAIL POST OFFICE TO ADDRESSEE" SERVICE UNDER 37 CFR 1 10 ON THE DATE INDICATED ABOVE AND IS ADDRESSED TO THE ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20211

PRINTED NAME JACQUELYN K TORBORG